

Title (en)  
METHOD FOR DEPOSITION OF TITANIUM OXIDE BY A PLASMA SOURCE

Title (de)  
VERFAHREN ZUR ABSCHIEDUNG VON TITANOXID DURCH EINE PLASMAQUELLE

Title (fr)  
PROCEDE DE DEPOT D'OXYDE DE TITANE PAR SOURCE PLASMA

Publication  
**EP 1644554 A1 20060412 (FR)**

Application  
**EP 04767517 A 20040630**

Priority  
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• FR 0307948 A 20030701

Abstract (en)  
[origin: FR2857030A1] The deposition on a substrate of a coating with a base of semiconductor metal oxide, preferably titanium oxide, is carried out by depositing the coating with photocatalytic properties using chemical deposition in the vapor phase, preferably from a gas mixture containing at least one organometallic and/or metallic halogen of the metal oxide precursor. The deposition is plasma assisted. Independent claims are also included for: (a) A substrate coated by the above method; (b) A monolithic, multiple or laminated anti-stain and/or anti-mist glazing incorporating the substrate.

IPC 1-7  
**C23C 16/40**

IPC 8 full level  
**C23C 16/40** (2006.01)

CPC (source: EP KR US)  
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